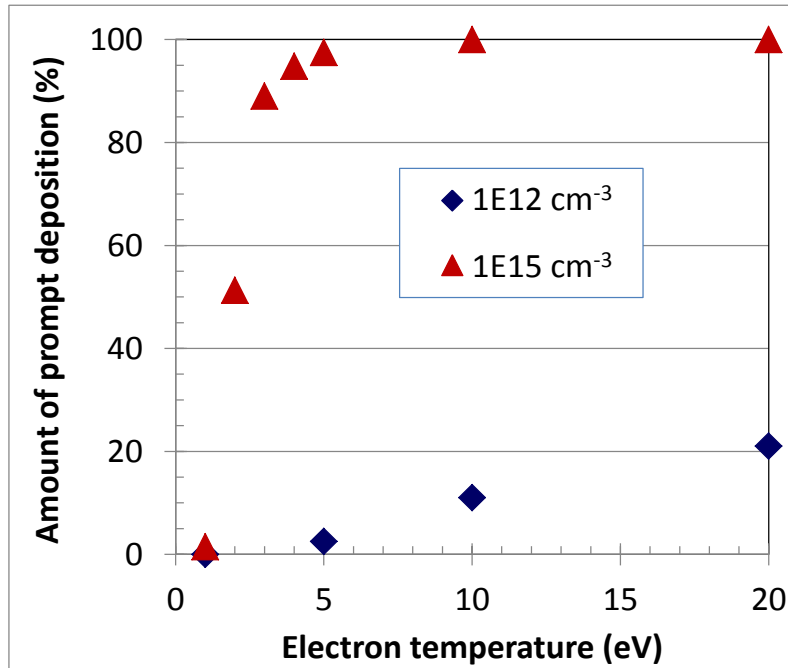


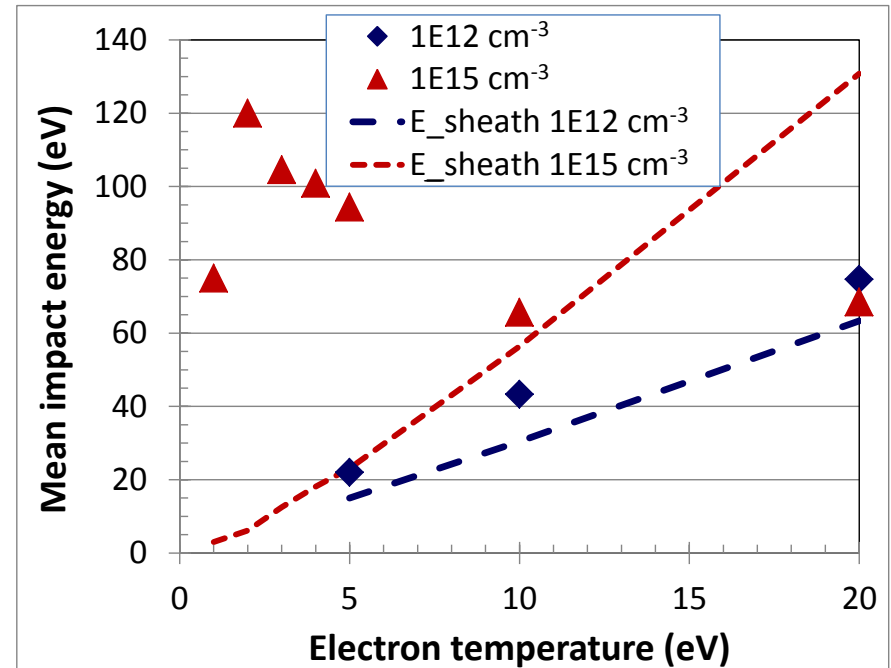
Modelling of Prompt Deposition of Tungsten under Fusion Relevant Conditions (TH/P6-22)

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Amount of prompt W deposition



Mean energy of promptly deposited W



- Modelled amount of prompt deposition with the ERO code varies from **0% to 47%** for 1E12 cm⁻³ and from **2% to 100%** for 1E15 cm⁻³.
- For high electron density and small electron temperature: modelled mean energy of promptly deposited W significantly larger than energy from sheath field – **entrainment**.
- Self-sputtering yield well below 1 for studied parameters: **no runaway sputtering**.